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Publication number:

0 441 373 A3

EUROPEAN PATENT APPLICATION

Application number: **91101682.2**

Int. Cl.⁵: **G01B 15/00, H01J 37/26**

Date of filing: **07.02.91**

Priority: **07.02.90 JP 28013/90**

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Date of publication of application:
14.08.91 Bulletin 91/33

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Designated Contracting States:
DE FR GB

Date of deferred publication of the search report:
16.12.92 Bulletin 92/51

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Method and apparatus for measuring pattern dimension.

A pattern dimension measuring method for measuring the dimension of a measuring portion of a pattern of a specimen (10) placed on a specimen stage (1d) by controlling a deflector (1b) of a scan type electron microscope (1) capable of setting a desired inclination angle of one of the specimen stage (1d) and a lens barrel, applying an electron beam to the measuring portion of the specimen (10), and image processing a secondary electron signal from the measuring portion, the method comprising: a first step of calculating the distance between top edges of the measuring portion of the pattern by image processing the secondary electron signal when the electron beam is applied to the measuring portion at an inclination angle of zero; a second step of obtaining the number of pixels at a taper portion of the measuring portion of the pattern by image processing the secondary electron signal when the electron beam is applied to the measuring portion at a first predetermined inclination angle which allows to observe the bottom edges; a third step of obtaining the number of pixels at the taper portion by image processing the secondary electron signal when the electron beam is applied to the measuring portion at a second predetermined inclination angle different from the first inclination angle which allows to observe the bottom edges; a fourth step of calculating the taper angle and height of the pattern in

accordance with the numbers of pixels of the taper portion obtained at the second and third steps and the first and second predetermined inclination angles; and a fifth step of calculating the distance between the bottom edges of the pattern and the difference ratio between the top edge and bottom edge distances in accordance with the results calculated at the fourth step.

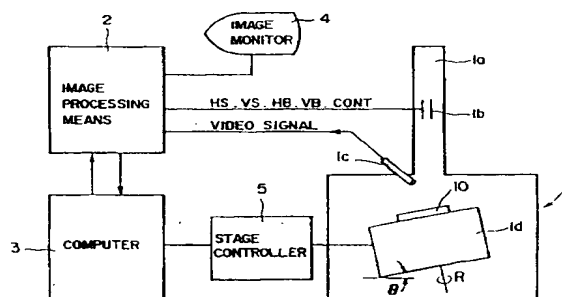


FIG. 1



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EUROPEAN SEARCH REPORT

Application Number

EP 91101682.2

DOCUMENTS CONSIDERED TO BE RELEVANT

Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl. 5)
A	EP - A - 0 345 772 (K.K. TOSHIBA) * Totality * --	1-5	G 01 B 15/04 G 01 B 15/00 H 01 J 37/26
A	US - A - 4 725 730 (KATO) * Fig. 5-9; column 3, line 27ff * ----	1-5	
			TECHNICAL FIELDS SEARCHED (Int. Cl. 5)
			G 01 B 15/00
The present search report has been drawn up for all claims			
Place of search VIENNA		Date of completion of the search 09-10-1992	Examiner TOMASELLI
CATEGORY OF CITED DOCUMENTS X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document			

EPO FORM 1503 03/82 (P/401)